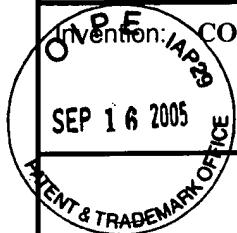


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(21) Application number : 06-049931 (71) Applicant : JAPAN SYNTHETIC RUBBER CO LTD

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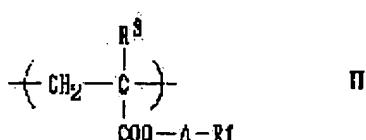
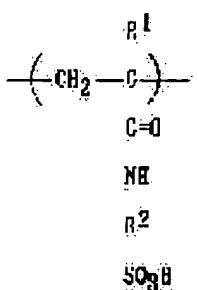
(54) BASE-INTERCEPTING ANTIREFLECTION FILM AND RESIST PATTERN FORMING METHOD

(57) Abstract:

PURPOSE: To improve resolution, developability, pattern formation and the efficiency of application by containing a specified copolymer and/or salt, and fluoroalkyl sulfonic acid and/or fluoroalkyl carboxylic acid.

CONSTITUTION: A base-intercepting antireflection film contains a copolymer having one kind of a repeat unit expressed by the formula I and one kind of a repeat unit expressed by the formula II and/or fluoroalkyl sulfonic acid having a fluoroalkyl group with the carbon number of 5-15 and/or fluoroalkyl carboxylic acid having a fluoroalkyl group with the carbon number of 5-15. In the formula I, R1 indicates a hydrogen atom or an organic group, and R2 indicates a bivalent organic group. In the formula II, R3 indicates a hydrogen atom or an organic group, Rf indicates a fluoroalkyl group, and A

up or a fluoroalkylene group. Thus, in the a basic material in the atmosphere can be wave effect can be reduced enough.



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